IAP20 Rec'd PCT/PTO 21 DEC 2005

Sheet <u>1</u> of <u>1</u>

Form PTO-1449 US Dept. of Commerce (REV. 8-83) PATENT & TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT				ATTY DOCKET NO. 126363			APPLICATION NO. New U.S. National Stage of PGT/JP2004/007/2528 65			
(Use several sheets if necessary)				APPLICANTS Nobuaki MITAMURA et al.						
·					FILING DATE December 21, 2005			GROUP 1.702		
	,	U.S	. PAT	ENT DOC	UMENTS					
EXAMINER INITIAL		DOCUMENT NUMBER		DATE	NAME		<u></u>	CLASS	SUB CLASS	
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	-	DOCUMENT NUMBER	!	DATE		COUNTRY		CLASS	CLASS	
R/H	1	JP A 11-147786 w/ abst & transl	6/2/1999		JAPAN					
FA.	2	JP A 2000-178099 w/ abst & transl	6/27/2000		JAPAN					
FA	3	JP A 2002-201093 w/ abst & transl	7/16	5/2002	JAPAN					
F 11	1	OTHER DOCUMENTS (In	cludin	g Author,	Title, Date, Per	rtinent Pages, etc.)				
БН.	4	VORONKOV, "The Mechanism of Swirl Defects Formation in Silicon," Journal of Crystal Growth, Vol. 59, pp. 625-643 {1982}								
F:#.	5	DUPRET et al., "Global Modelling of Heat Transfer in Crystal Growth Furnaces," Int. J. Heat Mass Transfer, Vol. 33, No. 9, pp. 1849-1871 {1990}								
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EXAMINER	<u></u>	Matter Considered (DA) 206								
Examiner: In	itial if	citation considered, whether or not ci	itation	is in con	formance with	M.P.E.P. 609; drav				
		ance and not considered. Include copy of	n inis	torm with	next communic	cation to applicant.				

Date: December 21, 2005